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AUG 0 9 2004 THE UNITED STATES PAT

THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Arkady Yampolsky and Masad

Art Unit : 3723

Aslan

Examiner: Lee Wilson

Serial No.: 09/903,052 Filed: July 10, 2001

Title : CLOSED-LOOP CONTROL OF A CHEMICAL MECHANICAL POLISIE

MAIL STOP PETITIONS

Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

PETITION TO WITHDRAW NOTICE OF ABANDONMENT

Under 37 CFR §§1.8(b) and 1.181, applicant hereby petitions to withdraw the Notice of Abandonment mailed July 22, 2004 (copy enclosed). The application was abandoned under 37 CFR §1.135 for failure to respond to the Office Action mailed September 26, 2003.

The undersigned, applicant's attorney of record, first became aware of the abandonment on August 2, 2004, on receipt of the Notice of Abandonment and submits that this petition to withdraw the Notice is being promptly submitted as required by 37 CFR §1.8(b)(1).

The following documents are submitted under 37 CFR §1.8(b)(2) as proof that a Response was timely filed on November 26, 2003:

- 1. A copy of a Response to Restriction Requirement, including an executed certificate of mailing signed by Carlos A. Brasil on November 26, 2003. The Response states "Enclosed is a check for \$110 for the Petition for One Month Extension of Time fee.";
- 2. A copy of a Preliminary Amendment, and including an executed certificate of mailing signed by Carlos A. Brasil on November 26, 2003;

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37 CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Date of Deposit

Eust 4, 2004

Signature

Nikia M. Mc Nillion

Typed or Printed Name of Person Signing Certificate

Applicant: Arkady Yampolsky and Masad Aslan

Attorney's Docket No.: 05542-443001 / 4738-2/CMP

Serial No.: 09/903,052 Filed: July 10, 2001

Page : 2 of 2

3. A copy of checks dated November 26, 2003, and postcard dated November 26, 2003, that were included with the Response; and

4. A copy of the postcard stamped received by the PTO Mailroom on November 28, 2003.

Applicant submits that the response to the Office Action was timely filed and requests that the Notice of Abandonment be withdrawn.

Please apply any charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date:	8/3/04	David G

David J. Goren Reg. No. 34,609

Telephone: (650) 839-5070 Facsimile: (650) 839-5071

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United States Patent and Tradema Address COMMISSIONER FOR PATI P.O. Box 1459 Alexandria, Virginia 22313-1450 www.uspio.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR Arkediy Yampolskiy	ATTORNEY DOCKET-NO. 004738/2/CMP	9389
	07/10/2001		EXAM WILSON	
2881 SCOTT E	ATERIALS, INC. BLVD. M/S 2061 A, CA 95050	COMPUTER ENTERED JUL 3 0 2004	3723	PAPER NUMBER
		Jur a a	DATE MAILED: 07/22/200	

Please find below and/or attached an Office communication concerning this application or proceeding

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filed 11/03

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	•		Applicant/s		
-		Application No.	Applicant(s)		
		09/903,052	YAMPOLSKIY ET AL.		
Notice of A	bandonment	Examiner	Art Unit		
		LEE D WILSON	3723		
- The MAILING DA	ATE of this communication app	pears on the cover sheet with the	correspondence address		
: This application is abandoned					
•		- I-was mailed on 26 Sentember 200	13		
(a) A reply was received	on (with a Certificate of	te letter mailed on <u>26 September 200</u> Mailing or Transmission dated month(s)) which expired on			
(L) [] A seemoned sorty wa	as received on but it does	s not coustitute a brober tebis mirger.	31 01 17 17 10 12		
application in condit	ion for allowance; (2) a timely file	on consists only of: (1) a timely filed and Notice of Appeal (with appeal fee); CFR 1.114).	, 0, (2, 2 0, 1, 2, 2, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1,		
(c) A reply was receive final rejection. See	(c) A reply was received on but it does not constitute a proper reply, or a bona fide attempt at a proper reply, to the non-final rejection. See 37 CFR 1.85(a) and 1.111. (See explanation in box 7 below).				
(d) 🖾 No reply has been r	eceived.				
from the mailing date of the issue fee and	f the Notice of Allowance (PTOL- publication fee, if applicable, we er the expiration of the statutory 5).	as received on (with a Certifi period for payment of the issue fee (in the statutory period of three months icate of Mailing or Transmission dated and publication fee) set in the Notice of		
(b) [] The submitted fee (of \$ is insufficient. A balan	ce of \$ is due.	- 0=D 4 40(4) in B		
The issue fee req	uired by 37 CFR 1.18 is \$	The publication fee, if required by 3)/ CFR 1.18(d), is \$		
	oublication fee, if applicable, has				
	3. Applicant's failure to timely file corrected drawings as required by, and within the three-month period set in, the Notice of Allowability (PTO-37). (a) Proposed corrected drawings were received on (with a Certificate of Mailing or Transmission dated), which is				
after the expiration	of the period for reply.	(With a Celulicate of Mailing of Th			
(b) No corrected drawi		·			
4. The letter of express abandonment which is signed by the attorney or agent of record, the assignee of the entire interest, or all of the applicants.					
1.34(a)) upon the filing	of a continuing application.	an attorney or agent (acting in a rep	_		
6. The decision by the B of the decision has ex	oard of Patent Appeals and Inter pired and there are no allowed c	ference rendered on and becalaims.	ause the period for seeking court review		
7. The reason(s) below:			/ WWW		
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minimize any negative effects	R 1.137(a) or (b), or requests to with on patent term.	hdraw the holding of abandonment under	37 CFR 1.181, should be promptly filed to		
U.S. Patent and Trademark Office PTOL-1432 (Rev. 04-01)		ce of Abandonment	Part of Paper No. 7		





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TECHNOLOGY CENTER FISTOR

Attorney's Docket No. 05542-443001		Mailing Date November 26, 2003	For PTO Use Only Do Not Mark in This Area
Application No. 09/903,052	Filing Date July 10, 2001	Attorney/Secretary Init DJG/THP/cab	
Title of the Invention CLOSED-LOOP C MECHANICAL PO	ONTROL OF A CHI	EMICAL	
Applicant Yampolsky et al. Client Reference No.			OIPE
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Attorney's Docket 05542-443001 / 4738-2/CMP

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Yampolsky et al.

Art Unit : 3723

Serial No.: 09/903,052

Examiner: Lee D. Wilson

Filed

: July 10, 2001

Title

CLOSED-LOOP CONTROL OF A CHEMICAL MECHANICAL POLISHER

Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Responsive to the action mailed September 26, 2003, applicant elects the invention of Group I (Claims 1-10) drawn to the embodiment of a method, classified in class 451, subclass 288. The election is made without traverse.

Enclosed is a check for \$110 for the Petition for One Month Extension of Time fee. Please apply any other appropriate charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Tim H. Pham Reg. No. 48,589

Telephone: (650) 839-5070 Facsimile: (650) 839-5071

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Date of Deposit

Signature

Carles A Brasil Typed or Printed Name of Person Signing Certificate

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Arkady Yampolsky and Masad

Art Unit: 3723

Aslan

Examiner: Lee D. Wilson

Filed

Serial No.: 09/903,052 : July 10, 2001

Title

: CLOSED-LOOP CONTROL OF A CHEMICAL MECHANICAL POLISHER

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Prior to examination, please amend the application as indicated on the following pages.

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November 26, 2003 Date of Deposit Signature

Carlos A. Brasil

Typed or Printed Name of Person Signing Certificate

Serial No.: 09/903,052 Filed: July 10, 2001

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Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

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Listing of Claims:

1. (Currently Amended) A method of controlling a chemical mechanical polishing system, comprising:

receiving an inner-tolerance, an outer tolerance and a specification tolerance limita plurality of tolerance limits;

receiving user input selecting one of the inner tolerance and the outer tolerance; receiving user input selecting a polishing machine procedure for the selected tolerance; polishing a first substrate with the chemical mechanical polishing system; measuring a thickness of at least one layer in the substrate at an in-line metrology station;

if the measured thickness exceeds the selected tolerance, performing the selected procedure

determining which, if any, of the tolerance limits are exceeded by the thickness measured; and

if it is determined that any of the tolerance limits are exceed, selecting one of a plurality of procedures of the chemical mechanical polishing system, the selection being based on a result of the determining step.

2. (Currently Amended) The method of claim 1, wherein the selected procedure plurality of procedures includes adjusting a polishing time of a second substrate from the same cassette as the first substrate.



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cont

3. (Currently Amended) The method of claim 1, wherein the selected procedure plurality of procedures includes adjusting a polishing time of a second substrate from a different cassette from the first substrate.

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- 4. (Currently Amended) The method of claim 1, wherein the selected procedure plurality of procedures includes displaying a warning message.
- 5. (Currently Amended) The method of claim 1, wherein the selected procedure includes generating plurality of procedures includes designating a gating substrate in the next cassette.
- 6. (Original) A method of chemical mechanical polishing, comprising: polishing a first substrate in a lot at a polishing station of a chemical mechanical polishing apparatus that includes an in-line metrology station;

measuring a thickness of at least one layer in the first substrate at the in-line metrology station; and

adjusting a polishing parameter based on the measurement of the first substrate; and polishing a second substrate at the polishing station with the adjusted polishing parameter.

- 7. (Original) The method of claim 6, wherein the thickness of the at least one layer is measured while a third substrate is being polished, and the second substrate is polished after the third substrate.
- 8. (Original) The method of claim 6, wherein the polishing parameter is adjusted if the measured thickness exceeds a tolerance limit.
 - 9. (Original) The method of claim 8, wherein the tolerance limit is entered by a user.

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10. (Original) The method of claim 6, wherein the polishing parameter is a polishing time.

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11-16. (Cancelled)

- 17. (New) The method of claim 1, wherein the selection is based on which of the plurality of tolerance limits are exceeded.
- 18. (New) The method of claim 1, wherein the plurality of tolerance limits includes an inner tolerance limit, and outer tolerance limit, and a specification tolerance limit.
- 19. (New) The method of claim 1, wherein the first substrate is one of a plurality of wafer types, the method further comprising:

receiving information identifying the wafer type of the first substrate, wherein the selection is based on the wafer type of the first substrate.

- 20. (New) The method of claim 1, wherein the plurality of wafer types includes a gating wafer type, a monitor wafer type, a regular wafer type, and a user defined wafer type.
- 21. (New) The method of claim 1, wherein the plurality of procedures include predefined procedures.
- 22. (New) The method of claim 1, wherein the plurality of procedures include one of immediately stopping polishing and idling, completing polishing of substrates currently loaded in the chemical mechanical polishing system and then idling, completing polishing of substrates in a cassette currently loaded in the chemical mechanical polishing system and then idling, adjusting a polishing time for other substrates in the cassette, adjusting the polishing time of substrates in other cassettes, requesting operator approval prior to adjusting the polishing time,

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Cont

requesting operator approval prior to adjusting a polishing procedure, returning the first substrate to the polishing apparatus, designating a gating group, generating a warning message, and generating a status message.

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23. (New) A chemical mechanical polishing system, comprising a controller configured to:

receive information specifying a wafer thickness;

determined which, if any of a plurality of tolerance limits are is exceeded by the wafer thickness; and

if any of the tolerance limits are exceeded, selecting a procedure of the system, the selection being based on which of the tolerance limits is exceeded.

- 24. (New) The system of claim 23, wherein the controller is further configured to: receive information specifying a wafer type; and the selection is further based on the wafer type specified.
- 25. (New) The system of claim 23, wherein the plurality of tolerance limits includes an inner tolerance limit, an outer tolerance limit, and a specification limit.
- 26. (New) The system of claim 23, wherein the wafer type is one of a gating wafer type, a monitor wafer type, a regular wafer type, and a user defined wafer type.
- 27. (New) A chemical mechanical polishing system, comprising a controller configured to:

receive information specifying a wafer thickness; receive information specifying one of a plurality of wafer types; determine if a tolerance limit is exceeded by the wafer thickness; and

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cont

if the tolerance limit is exceeded, selecting a procedure of the system, the selection being based on the wafer type specified.

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28. (New) The system of claim 27, wherein the plurality of wafer types includes a gating wafer type, a monitor wafer type, a regular wafer type, and a user defined wafer type.

29. (New) The system of claim 27, wherein there are more than one tolerance limits and the selection is further based on which tolerance limit is exceeded.

30. (New) The system of claim 29, wherein the tolerance limits include an inner tolerance limit, an outer tolerance limit, and a specification tolerance limit.

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REMARKS

The applicant asks that all claims be examined in view of the above amendments.

Attached is a \$72 check for the excess claims fee. Please apply any other appropriate charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: Novantre 26, 2003

Tim H. Pham Reg. No. 48,589

Telephone: (650) 839-5070 Facsimile: (650) 839-5071

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Attorney's Docket No. 05542-443001		Mailing Date November 26, 2003	For PTO Use Only Do Not Mark in This Area
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